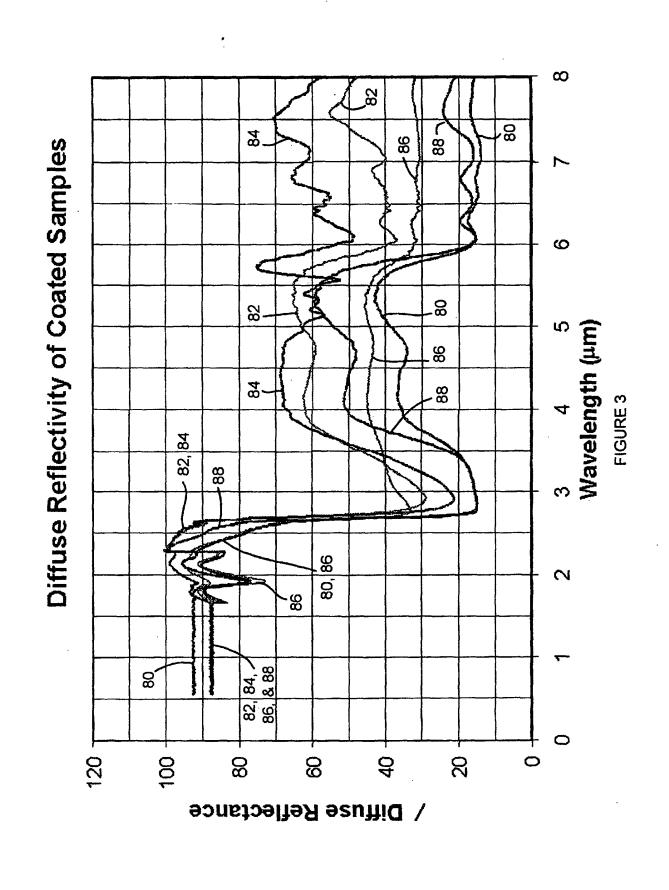
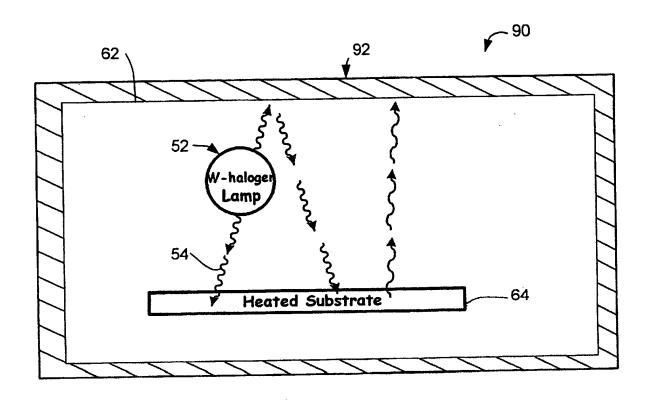


FIGURE 2





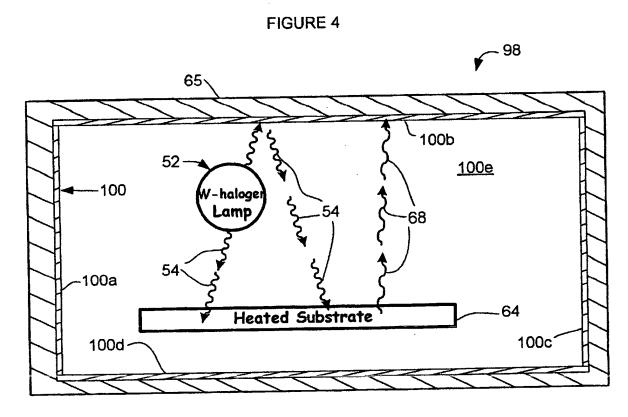
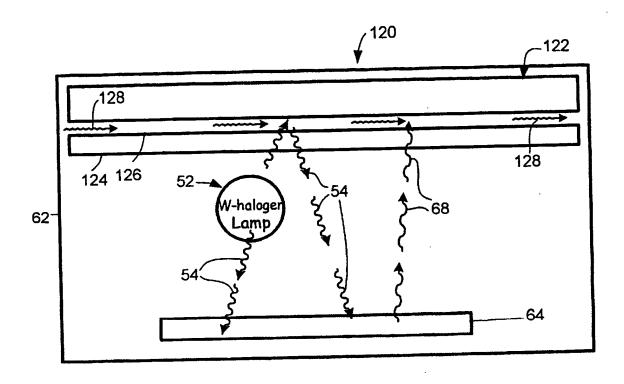


FIGURE 5





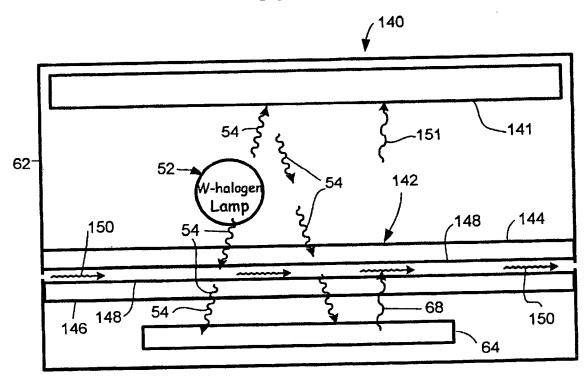
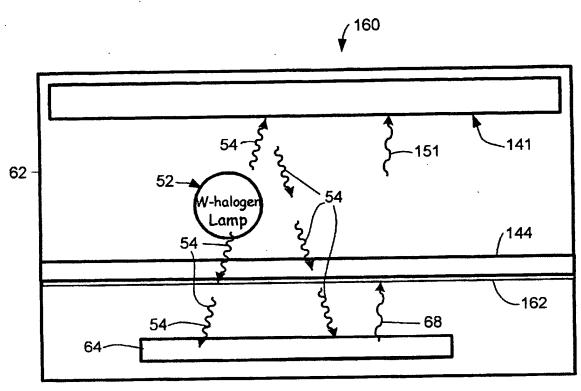


FIGURE 7



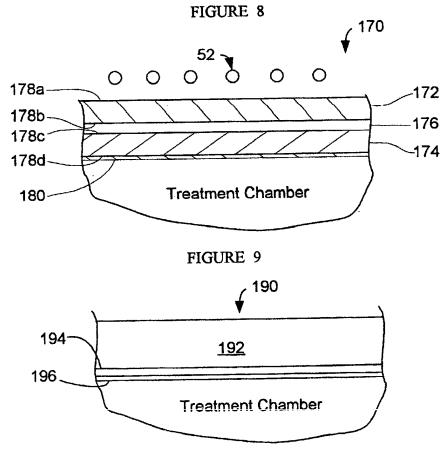
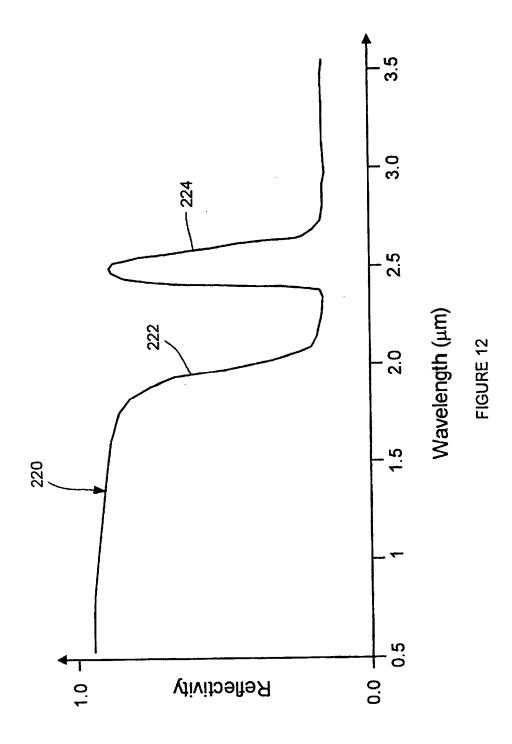


FIGURE 10

USJ "Spike" Anneal Peak-Width Improvement for 300-mm Wafers 200 5: Time (Sec.) 202 ΔT_2 (O°) eruter (°C) $\frac{8}{8}$ 950 1100 1

FIGURE 11



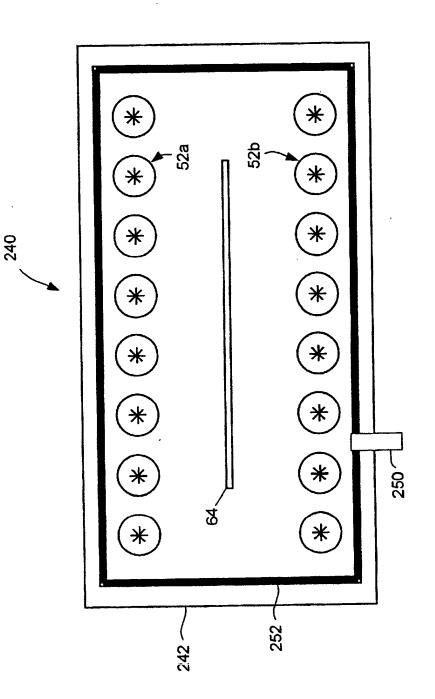
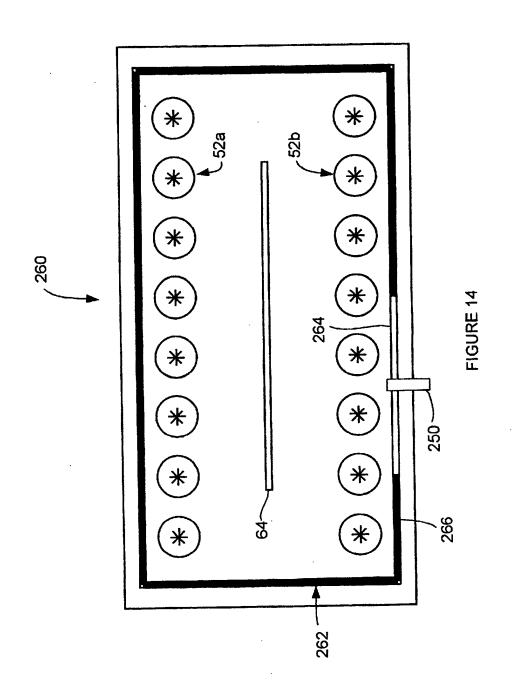


FIGURE 13



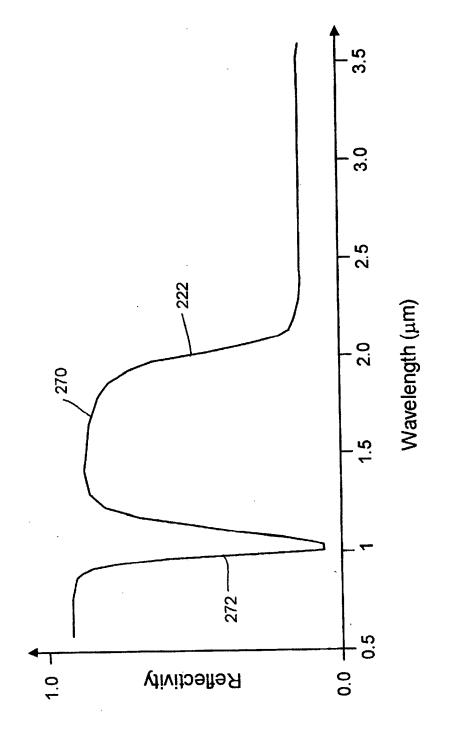
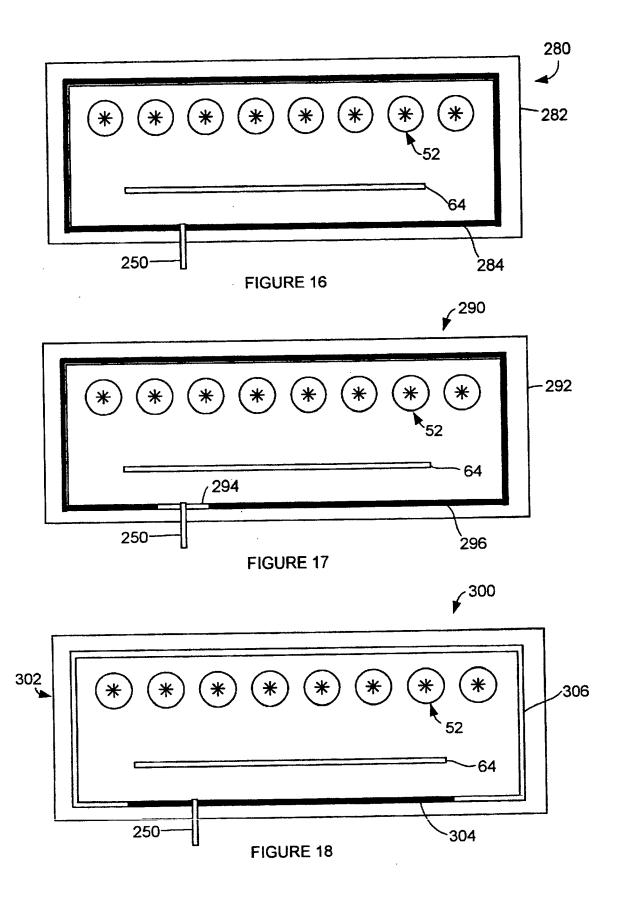
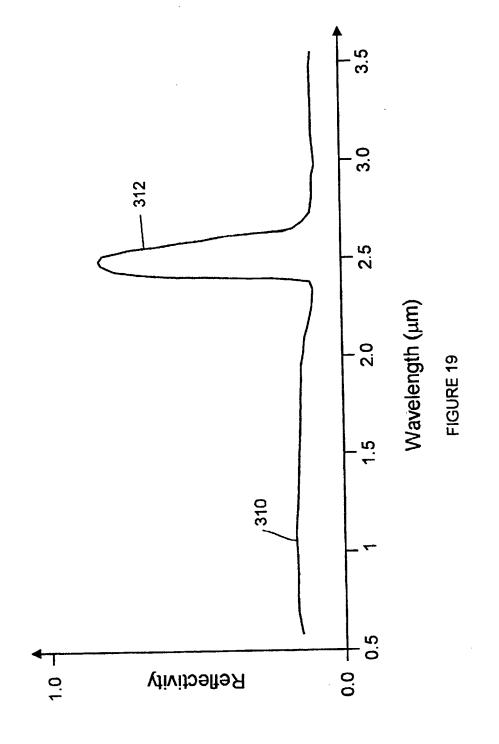
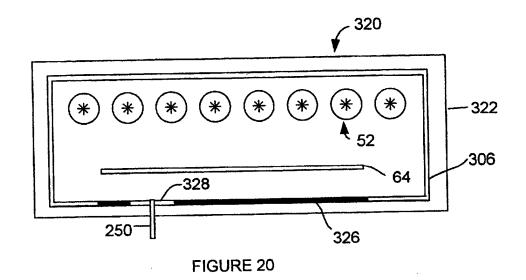


FIGURE 15







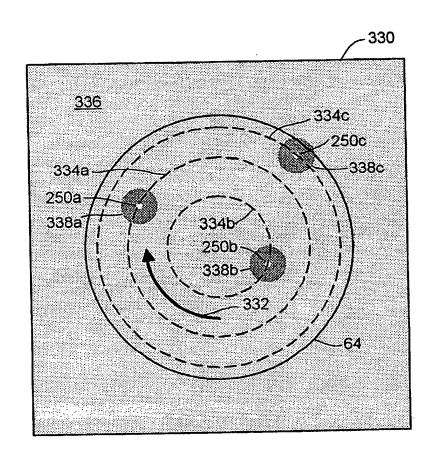


FIGURE 21